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On: JUNE 2, 2000

By:

LINDA E. HASTINGS

Any fee due as a result of this paper, not covered by an enclosed check, may be charged on Deposit Acct. No. 08-1634.

Attorney Docket No.:NEKW14.868

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

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Assistant Commissioner for Patents
Washington, D.C. 20231

PETITION FOR EXTENSION OF TIME

S I R :

Applicant requests that the time for taking action in this case be extended pursuant to 37 CFR 1.136(a) for:

☒ one month

☐ three months

☐ two months

☐ four months

The fee set in 37 CFR 1.17 for the extension of time is \$110.00.

☒ Fee enclosed. Please charge any additional fee required for this extension of time to Deposit Account No. 08-1634. A duplicate copy of this paper is enclosed.

☐ Charge fee to Deposit Account No. 08-1634. A duplicate copy of this paper is enclosed.

☐ Applicant is a small entity entitled to pay reduced fees in this application. A verified small entity statement:

☐ has been filed

☐ is enclosed

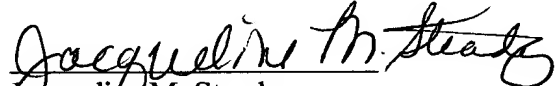
Also enclosed is a:

☒ Response to Official Action

☐ Notice of Appeal

☐ Appeal Brief

Respectfully submitted,


Jacqueline M. Steady
Reg. No. 44,354

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